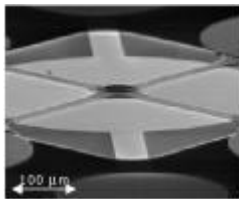


### Fine Pointing Device for Intersatellite Link

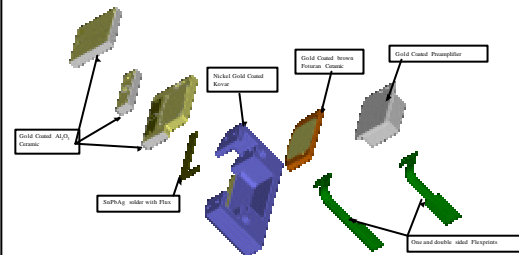
Alex Dommann



The strong demand for MEMS and Microsystems by a rapidly growing market has generated strong interest in quality control and failure analysis.



### Schematic scheme for the Sensor Block FPA



### Structuring of Foturan Ceramic



Structuring  
Of the Foturan with UV Light

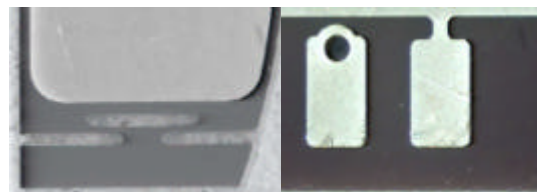


Recrystallization  
between 500° and 600°C



Etching  
10% HF at RT 20 x faster

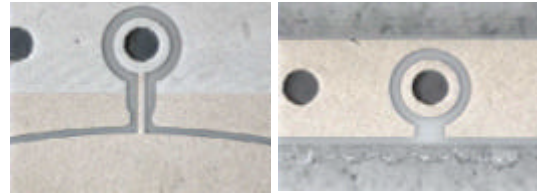
### Driver Plates



### Foturan with Flexprint



### Upper and middle sensor Plate



### Lower Sensor Plate



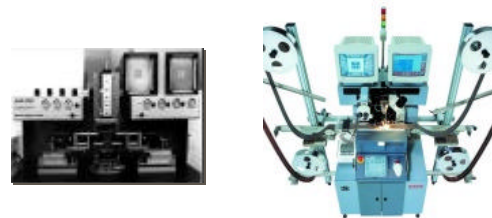
### Infrastructure of the Institute



### Coating equipment



### Bonding and Packaging



**Etch- and Liftoff Process** 1 μS

**Etch - Process**

1. Clean substrate
2. Metallization sputtered Al (evaporated Al)
3. Photoresist Spin - coating
4. UV-Light Exposure through mask
5. Development of exposure resist
6. Etch step wet etch (isotropic) dry etch (isotropic) remove of resist

**Liftoff - Process**

1. Clean substrate
2. Deposition of photoresist Spin - coating
3. UV-light exposure and development of resist
4. Metallization evaporated Al (defined angle of incidence)
5. Lift off Remove photoresist to get final structure

**Analysis** 1 μS

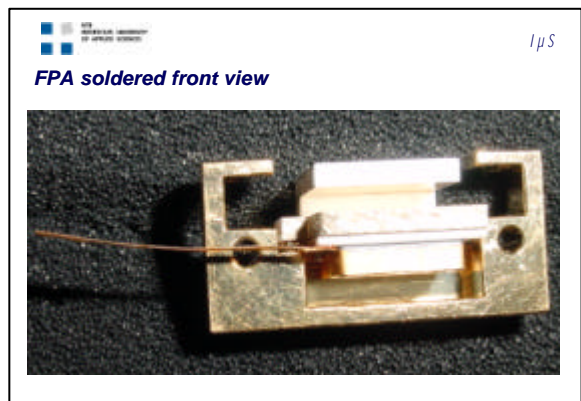
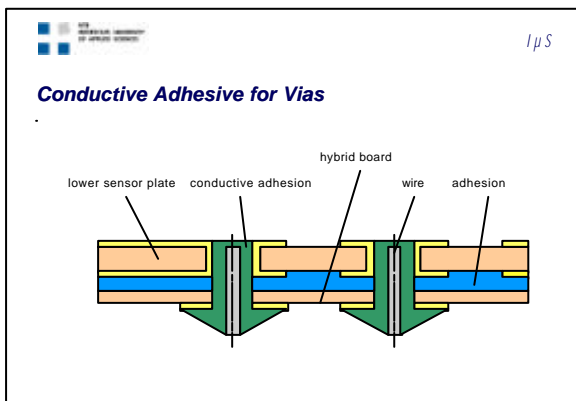
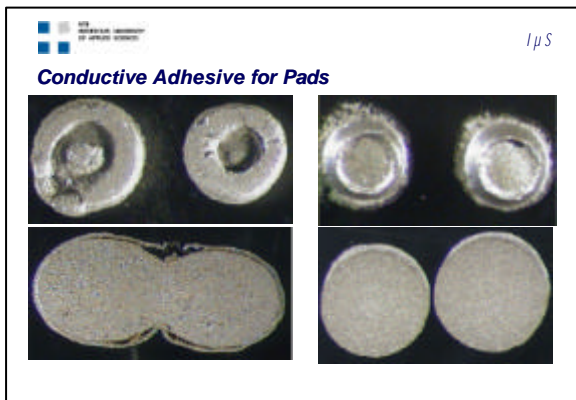
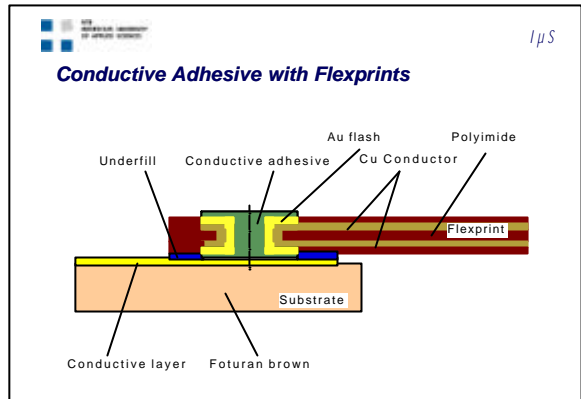
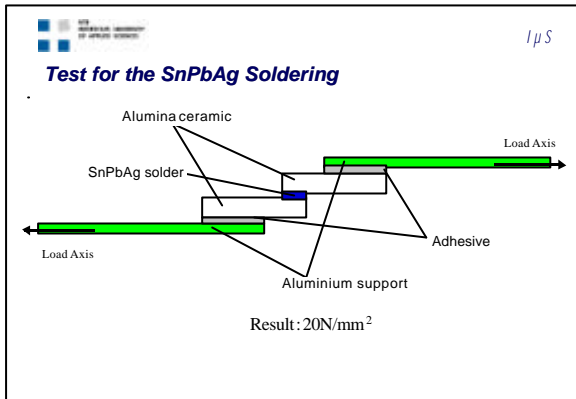
**AFM Measurement** 1 μS

**SEM** 1 μS

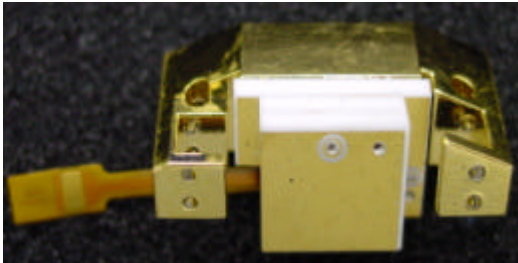
**Test for the AuSn Soldering** 1 μS

Results:  
30N/mm<sup>2</sup> to 65N/mm<sup>2</sup>

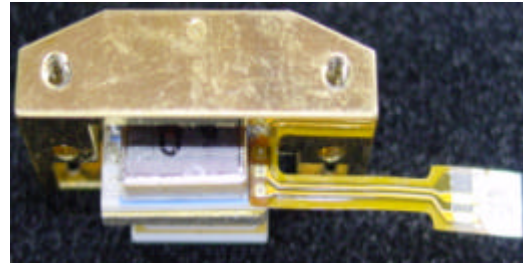
**Cross-section through the AuSn Soldering**



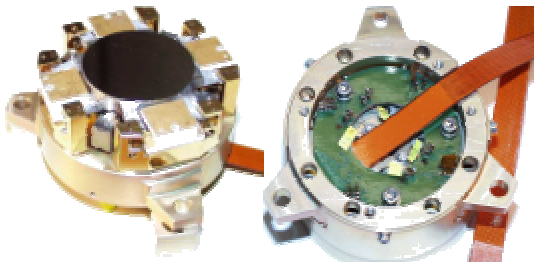
**FPA soldered top**



**FPA soldered down**



**Fine Pointing Assembly**



**FPA with Cover**



**Complete FPA ready for Mounting**



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